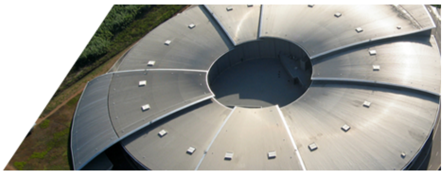

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Thin, low roughness Ru films deposited by thermal and plasma enhanced atomic layer deposition using RuO_4 and H_2 at low temperatures

Tuesday, 14 June 2016 17:00 (20 minutes)

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